Amendments to the Claims:

1. (currently amended) A ~~solvent~~ **CVD precursor** solution including **a solvent component and** a hexacoordinated silicon beta-diketonate composition of the formula $R_2Si(\beta\text{-diketonate})_2$ or $(RO)_2Si(\beta\text{-diketonate})_2$, wherein each R is the same as or different from the other R, and each R is independently selected from H, aryl, fluoroaryl, $C_1 - C_{12}$ alkyl, $C_1 - C_{12}$ fluoroalkyl, and $C_1 - C_{12}$ silicon-containing alkyl.

2. (currently amended) The ~~solvent~~ **precursor** solution of claim 1, wherein each ß -diketonate ligand of the composition may be the same as or different from the other ß -diketonate ligand of the composition, and is independently selected from: 2,2,6,6-tetramethyl-3,5-heptanedionate; 1,1,1,2,2,3,3-hepta-fluoro-7,7-dimethyloctane-4,6-dionate; acetylacetonate; trifluoro-acetylacetonate; and hexafluoroacetylacetonate.

3. (currently amended) The ~~solvent~~ **precursor** solution of claim 1, wherein each ß -diketonate ligand of the composition is 2,2,6,6-tetramethyl-3,5-heptanedionate.

4. (currently amended) The ~~solvent~~ **precursor** solution of claim 1, wherein the composition is of the formula $R_2Si(\beta\text{-diketonate})_2$.

5. (currently amended) The ~~solvent~~ **precursor** solution of claim 1, wherein the composition is of the formula $(RO)_2Si(\beta\text{-diketonate})_2$.

6. (currently amended) The ~~solvent~~ **precursor** solution of claim 1, wherein the composition is of the formula $(t\text{-BuO})_2Si(2,2,6,6\text{-tetramethyl-3,5-heptanedionate})_2$.

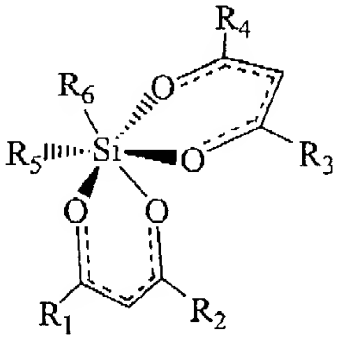
7. (currently amended) The ~~solvent~~ **precursor** solution of claim 1, wherein the composition is of the formula $(CH3)_2Si(2,2,6,6\text{-tetramethyl-3,5-heptanedionate})_2$.

8. (previously canceled)

9. (currently amended) The ~~solvent~~ **precursor** solution of claim 1**, wherein said solvent component comprises** ~~including~~ a hydrocarbon solvent.

10. (currently amended) The ~~solvent~~ **precursor** solution of claim 1**, wherein said solvent component comprises** ~~including~~ octane.

11. (currently amended) A **precursor solution for use in chemical vapor deposition, comprising a solvent component and a** silicon ß -diketonate ~~for use in chemical vapor deposition and~~ of the formula:

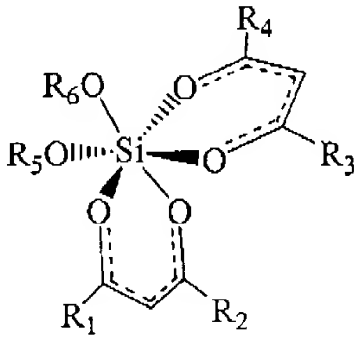


wherein:

R_1, R_2, R_3 and R_4 are the same as or different from one another, and wherein each of such substituents is independently selected from H, aryl, fluoroaryl, $C_1 - C_{12}$ alkyl, $C_1 - C_{12}$ fluoroalkyl, and $C_1 - C_{12}$ silicon-containing alkyl; and

R_5 and R_6 are same as or different from one another, and each is independently selected from H, aryl, fluoroaryl, $C_1 - C_{12}$ alkyl, $C_1 - C_{12}$ fluoroalkyl, and $C_1 - C_{12}$ silicon-containing alkyl.

12. (currently amended) A **precursor solution for use in chemical vapor deposition, comprising a solvent component and a** silicon ß -diketonate ~~**for use in chemical vapor deposition and**~~ of the formula:



wherein:

R_1, R_2, R_3 and R_4 are the same as or different from one another, and wherein each of such substituents is independently selected from H, aryl, fluoroaryl, $C_1 - C_{12}$ alkyl, $C_1 - C_{12}$ fluoroalkyl and $C_1 - C_{12}$ silicon-containing alkyl; and

R_5 and R_6 are same as or different from one another, and each is independently selected from H, aryl, fluoroaryl, $C_1 - C_{12}$ alkyl, $C_1 - C_{12}$ fluoroalkyl, and $C_1 - C_{12}$ silicon-containing alkyl.

13-34. (previously canceled)

35. (new) A novel composition comprising $(t\text{-}OBu)_2Si(thd)_2$.

36. (new) A novel composition comprising $(CH_3)_2Si(thd)_2$.